Online Examinations (Even Sem/Part-I/Part-II Examinations 2020 - 2021

Course Name - -VLSI Devices and Design Course Code - PCC-EC603

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8.

Mark only one oval.
Diploma in Pharmacy
Bachelor of Pharmacy
B.TECH.(CSE)
B.TECH.(ECE)
BCA
B.SC.(CS)
B.SC.(BT)
B.SC.(ANCS)
B.SC.(HN)
B.Sc.(MM)
B.A.(MW)
BBA
B.COM
B.A.(JMC)
BBA(HM)
BBA(LLB)
B.OPTOMETRY
B.SC.(MB)
B.SC.(MLT)
B.SC.(MRIT)
B.SC.(PA)
LLB
B.SC(IT)-AI
B.SC.(MSJ)
Bachelor of Physiotherapy
B.SC.(AM)
Dip.CSE
Dip.ECE
<u>DIP.EE</u>
DIPCE

9.

	Offine Examinations (Even being arein arein Examinations 2020 - 20
DIP.ME	
PGDHM	
MBA	
M.SC.(BT)	
M.TECH(CSE)	
LLM	
M.A.(JMC)	
M.A.(ENG)	
M.SC.(MATH)	
M.SC.(MB)	
MCA	
M.SC.(MSJ)	
M.SC.(AM)	
M.SC.CS)	
M.SC.(ANCS)	
M.SC.(MM)	
B.A.(Eng)	
Answer all the questions.	Each question carry one mark.
. 1. Moore was co-found	der of
Mark only one oval.	
TCS	
Infosys	
Intel	
Wipro	

10.	2. Medium scale integration has logic gates.
	Mark only one oval.
	13 to 99
	1 to 12
	100 to 9,999
	10,000 to 99,999
11.	3. As die size shrinks, the complexity of making the photomasks
	Mark only one oval.
	increases
	decreases
	remains the same
	cannot be determined
12.	4. What is the design flow of VLSI system? i. architecture design ii. circuit design iii.
	logic design iv. physical design
	Mark only one oval.
	ii-i-iii-iv
	iv-i-iii-ii
	iii-ii-i-iv
	i-iii-iiv

13.	5. Which is the high level representation of VLSI design?
	Mark only one oval.
	architect design
	logic design
	circuit design
	physical design
14.	6. Gate minimization technique is used to simplify the logic.
	Mark only one oval.
	true
	false
	In the case of Silicon, even if the number of the gate is minimised, logic will not be simplified
	In the case of Ge, even if the number of the gate is minimised, logic will not be simplified
15.	7. nMOS fabrication process is carried out in
	Mark only one oval.
	thin wafer of a single crystal
	thin wafer of multiple crystals
	thick wafer of a single crystal
	thick wafer of a multiple crystal

10.	patterned.
	Mark only one oval.
	insulating
	conducting
	silicon
	semiconducting
17.	9. In nMOS device, gate material could be
	Mark only one oval.
	silicon
	polysilicon
	boron
	phosphorus
18.	10. Electronics are characterized by
	Mark only one oval.
	low cost
	low weight and volume
	reliability
	low cost, low weight and volume, reliability

19.	11. nMOS devices are formed in
	Mark only one oval.
	p-type substrate of high doping level
	n-type substrate of low doping level
	p-type substrate of moderate doping level
	n-type substrate of high doping level
20.	12. Source and drain in nMOS device are isolated by
	Mark only one oval.
	a single diode
	two diodes
	three diodes
	four diodes
21.	13. What is the condition for non saturated region?
	Mark only one oval.
	Vds = Vgs - Vt
	Vgs lesser than Vt
	Vds lesser than Vgs - Vt
	Vds greater than Vgs – Vt

22.	14. What is the condition for non conducting mode?
	Mark only one oval.
	Vds lesser than Vgs
	Vgs lesser than Vds
	Vgs = Vds = 0
	Vgs = Vds = Vs = 0
23.	15. MOS transistor structure is
	Mark only one oval.
	symmetrical
	non symmetrical
	semi symmetrical
	pseudo symmetrical
24.	16. Which is the commonly used bulk substrate in nMOS fabrication?
	Mark only one oval.
	either bulk silicon or silicon-on-sapphire
	silicon-di-oxide
	aluminium
	copper

25.	17. Contact cuts are made in
	Mark only one oval.
	only source
	only drain
	source, drain and gate
	diffusion layer
26.	18. Sllicon-di-oxide is a good insulator.
	Mark only one oval.
	True
	False
	Sometimes
	Never
	Never
27.	19. In nMOS, is used to suppress unwanted conduction.
	Mark only one oval.
	phosphorus
	boron
	silicon
	oxygen
	,-

28.	20. The FPGA refers to
	Mark only one oval.
	First programmable Gate Array Field Program Gate Array First Program Gate Array Field Program Gate Array
29.	21. In which design, all circuitry and all interconnections are designed? Mark only one oval. full custom design semi-custom design gate array design transistor design
30.	22. In which method regularity is used to reduce complexity? Mark only one oval. random approach hierarchical approach algorithmic approach semi-design approach

31.	23. Which design is faster?
	Mark only one oval.
	full custom design semi-custom design
	gate array design
	transistor design
32.	24. Which type of simulation mode is used to check the timing performance of a design?
	Mark only one oval.
	Behavioural
	Switch-level
	Transistor-level
	Gate-level
33.	25. Which type of device FPGA is?
	Mark only one oval.
	SLD
	SROM
	EPROM
	PLD

34.	26. In FPGA, vertical and horizontal directions are separated by
	Mark only one oval.
	A line A channel A strobe A flip-flop
35.	27. The inputs in the PLD is given through
	Mark only one oval.
	NAND gates OR gates NOR gates AND gates
36.	28. The n-type semiconductor have as majority carriers. Mark only one oval. Holes Negative ions Electrons Positive ions

37.	29. The majority carriers of p-type semiconductor are:
	Mark only one oval.
	Holes Negative ions Electrons Positive ions
38.	30. The n-MOS transistor is made up of:
	Mark only one oval.
	N-type source, n-type drain and p-type bulk N-type source, p-type drain and p-type bulk P-type source, n-type drain and n-type bulk P- type source, p-type drain and n-type bulk
39.	31. The drain current is varied by:
	Mark only one oval.
	Gate to source voltage Gate current Source Voltage None of the mentioned

40.	32. The n-MOSFET is working as accumulation mode when:
	Mark only one oval.
	Gate is applied with positive voltage Gate is grounded
	Gate is applied with a negative voltage
	Gate is connected to the source
41	22 Miliah MOCETTia arang mellanggan da dia a singgita
41.	33. Which MOSFET is generally grounded in a circuit?
	Mark only one oval.
	PMOS
	NMOS
	CMOS
	DMOS
42.	34. The current through the n-MOS transistor will flow when:
	Mark only one oval.
	Vgs > Vtreshold, Vds=0
	Vgd < Vtreshold, Vds=0
	Vgs > Vtreshold, Vds>0
	Vgd > Vtreshold, Vds<0

43.	source voltage iii) Bulk to source voltage iv) Threshold voltage v) Dimensions of MOSFET
	Mark only one oval.
	Only i
	Only i, ii and iii
	Only v
	All of the mentioned
4.4	2/ If the a MOC and a MOC of the CMOC inventors are interesting and the contract in
44.	36. If the n-MOS and p-MOS of the CMOS inverters are interchanged the output is measured at:
	Mark only one oval.
	Source of both transistor
	Drains of both transistor
	Drain of n-MOS and source of p-MOS
	Source of n-MOS and drain of p-MOS
45.	37. What will be the effect on output voltage if the positions of n-MOS and p-MOS in CMOS inverter circuit are exchanged?
	Mark only one oval.
	Output is same
	Output is reversed
	Output is always high
	Output is always low

40.	38. The CIVIOS Inverter consists of:
	Mark only one oval.
	Enhancement mode n-MOS transistor and depletion mode p-MOS transistor
	Enhancement mode p-MOS transistor and depletion mode n-MOS transistor
	Enhancement mode p-MOS transistor and enhancement mode p-MOS transistor
	Enhancement mode p-MOS transistor and enhancement mode n-MOS transistor
47.	39. When the input of the CMOS inverter is equal to Inverter Threshold Voltage Vth, the transistors are operating in:
	Mark only one oval.
	N-MOS is cutoff, p-MOS is in Saturation
	P-MOS is cutoff, n-MOS is in Saturation
	Both the transistors are in linear region
	Both the transistors are in saturation region
48.	40. Which of these invertors is more efficient?
	Mark only one oval.
	Depletion mode n-MOS inverter
	pMOS inverter
	CMOS inverter
	Resistive load nMOS inverter

49.	41. The Fermi potential is the function of:
	Mark only one oval.
	Temperature Doping concentration
	Difference between Fermi level and intrinsic Fermi level
	All of the mentioned
50.	42. In positive logic convention, the true state is represented as:
	Mark only one oval.
	1
	0
51.	43. In CMOS logic circuit, the switching operation occurs because:
	Mark only one oval.
	Both n-MOSFET and p-MOSFET turn OFF simultaneously for input '0' and turn ON simultaneously for input '1'
	Both n-MOSFET and p-MOSFET turn ON simultaneously for input '0' and turn OFF simultaneously for input '1'
	N-MOSFET transistor turns ON, and p-MOSFET transistor turns OFF for input '1' and N-MOS transistor turns OFF, and p-MOS transistor turns ON for input '0'
	None of the mentioned

52.	44. When both nMOS and pMOS transistors of CMOS logic gates are ON, the output is:
	Mark only one oval.
	1 or Vdd or HIGH state
	0 or ground or LOW state
	Crowbarred or Contention(X)
	None of the mentioned
50	45. Tatal associa a section state in a balf adding
53.	45. Total number of inputs in a half adder is
	Mark only one oval.
	2
	3
	4
	1
54.	46. If A and B are the inputs of a half adder, the sum is given by
	Mark only one oval.
	A AND B
	A OR B
	A XOR B
	A EX-NOR B

55.	47. Half-adders have a major limitation in that they cannot
	Mark only one oval.
	Accept a carry bit from a present stage
	Accept a carry bit from a next stage
	Accept a carry bit from a previous stage
	Accept a carry bit from the following stages
56.	48. If A, B and C are the inputs of a full adder then the sum is given by
	Mark only one oval.
	A AND B AND C
	A OR B AND C
	A XOR B XOR C
	A OR B OR C
57.	49. How many AND, OR and EXOR gates are required for the configuration of full adder?
	Mark only one oval.
	1, 2, 2
	2, 1, 2
	3, 1, 2
	4, 0, 1

58.	50. Latch is a device with
	Mark only one oval.
	One stable state
	Two stable state
	Three stable state
	Infinite stable states
59.	51. Two stable states of latches are
	Mark only one oval.
	Astable & Monostable
	Low input & high output
	High output & low output
	Low output & high input
60.	52. The full form of SR is
	Mark only one oval.
	System rated
	Set reset
	Set ready
	Set Rated

61.	53. The outputs of SR latch are
	Mark only one oval.
	x and y
	a and b
	s and r
	q and q'
62.	54. CMOS technology is used in developing which of the following?
	Mark only one oval.
	microprocessors
	microcontrollers
	digital logic circuits
	all of the mentioned
63.	55. In CMOS fabrication, nMOS and pMOS are integrated into the same substrate.
	Mark only one oval.
	true
	false
	can't be determined
	sometimes true sometimes false

64.	56. Oxidation process is carried out using
	Mark only one oval.
	high purity oxygen low purity oxygen
	sulphur
	nitrogen
65.	57. In CMOS fabrication, the photoresist layer is exposed to
	Mark only one oval.
	visible light
	ultraviolet light
	infrared light
	fluorescent
66.	58. P-well doping concentration and depth will affect the
	Mark only one oval.
	threshold voltage
	Vss
	Vdd
	Vgs

67.	59. N-well is formed by
	Mark only one oval.
	decomposition
	diffusion
	dispersion
	filtering
68.	60. Which statement is false concerning Moore's Law?
	Mark only one oval.
	The term was named for Gordon Moore.
	Gordon Moore was one of the founders of IBM.
	In the 1960s the storage density of integrated circuits on a silicon chip doubled about every year.
	Today, when we speak of Moore's Law we refer to the doubling of computer power every 18 months.
69.	61. How many gates per chip are used in first-generation Integrated Circuits?
	Mark only one oval.
	3-30
	30-300
	300-3000
	More than 3000

70.	62. MOS transistors consist of which of the following?
	Mark only one oval.
	semiconductor layer metal layer
	layer of silicon-di-oxide
	all of the mentioned
71.	63. The gate region of transistor does not consist of
	Mark only one oval.
	semiconductor layer
	insulating layer
	metal layer
	ground layer
72.	64. In N channel MOSFET which is the more negative of the elements?
	Mark only one oval.
	source
	gate
	drain
	source and drain

73.	65. Enhancement mode device acts as switch, depletion mode acts as switch.
	Mark only one oval.
	open, closed
	closed, open
	open, open
	close, close
74.	66. In P channel MOSFET which is the more positive of the elements?
	Mark only one oval.
	a. source
	b. gate
	c. drain
	d. source and drain
75.	67. In the inverter circuit, the output is taken from which part of nMOS and pMOS?
	Mark only one oval.
	source - source
	drain - drain
	source - drain
	drain - source

76.	68. Which component is added to the p-type material in order to get the impurity concentration in epitaxial films?
	Mark only one oval.
	Bi-borane (B2H2)
	Phosphine (PH3)
	Boron chloride (BCl3)
	Phosphorous pentoxide (P205)
77.	69. Which of the following is used to obtain silicon crystal structure while
	fabricating Integrating Circuits?
	Mark only one oval.
	Oxidation
	Epitaxial growth
	Photolithography
	Glass wafer preparations
78.	70. For oxidation process, silicon wafers are heated to a high temperature and simultaneously they are exposed to a gas containing
	Mark only one oval.
	H20
	Si
	N2
	H2

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